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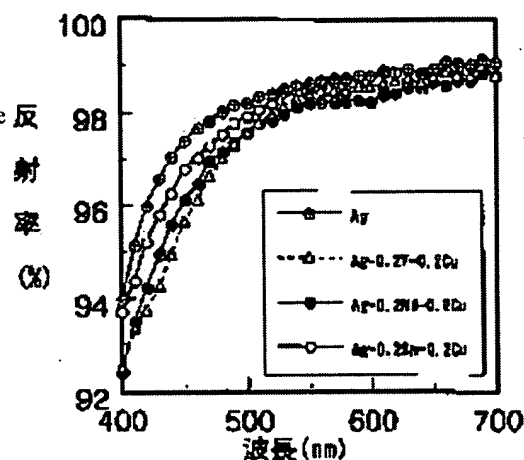
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## (54) PLANAR DISPLAY UNIT, Ag ALLOY-BASED REFLECTIVE FILM THEREFOR AND SPUTTERING TARGET MATERIAL FOR Ag ALLOY- BASED REFLECTIVE FILM FORMATION

(57)Abstract:

PROBLEM TO BE SOLVED: To provide an Ag alloy-based reflective film improving adhesion and patterning to a substrate, by making a reflectance a constant value in a visible range after maintaining a high reflectance and providing thermal resistance and corrosive resistance, and to provide a sputtering target material for forming the Ag alloy-based reflective film, and a high quality and low power consumption planar display unit.

SOLUTION: The Ag alloy-based reflective film for the planar display unit comprises 0.1-0.5 at.% of Sm, 0.1-0.5 at.% in total of Au and/or Cu, and the residue of substantially Ag. In addition, the planar display unit uses the Ag alloy-based reflective film having the above composition. The sputtering target material for the Ag alloy-based reflective film comprises 0.1-0.5 at.%, 0.1-0.5 at.% in total of Au and/or Cu, and the residue of substantially Ag.



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